

REMARKS

35 USC 102

Claims 1-3 are rejected under 35 USC 102(b) as being anticipated by Nakabayashi et al. (US 2002/0033381). The Applicant respectfully disagrees, especially based on the amendments presented herein.

Claim 1 recites:

“A used PVD component refurbishing method comprising:

providing a used PVD component having a layer deposited on a component surface, wherein the component comprises a tantalum coil and the deposited layer comprises TaN deposited on the coil surface during PVD use;

first etching the deposited layer using a first acid-comprising etchant;

after the first etching, entraining abrasive particles in a flow of gas, impinging the particles on the etched layer, and abrading the etched layer; and

after the abrading, second etching the abraded layer using a second acid-comprising etchant.”

Nakabayashi does not disclose that the component comprises a tantalum coil and that the deposited layer comprises TaN deposited on the coil surface. Therefore, claim 1 is not anticipated by Nakabayashi and claims 2-3 are not anticipated by Nakabayashi based on their dependency on claim 1.

Claims 1-3, 9, 11 and 15 are rejected under 35 USC 102(e) as being anticipated by Takahashi et al. (US 6902814). The Applicant respectfully disagrees, especially based on the amendments

presented herein.

Claim 1 recites:

“A used PVD component refurbishing method comprising:

providing a used PVD component having a layer deposited on a component surface, wherein the component comprises a tantalum coil and the deposited layer comprises TaN deposited on the coil surface during PVD use;

first etching the deposited layer using a first acid-comprising etchant;

after the first etching, entraining abrasive particles in a flow of gas, impinging the particles on the etched layer, and abrading the etched layer; and

after the abrading, second etching the abraded layer using a second acid-comprising etchant.”

Takahashi does not disclose that the component comprises a tantalum coil and that the deposited layer comprises TaN deposited on the coil surface. Therefore, claim 1 is not anticipated by Takahashi and claims 2-3, 9, 11 and 15 are not anticipated by Takahashi based on their dependency on claim 1.

35 USC 103

Claim 5 (claims 4 and 8 are herein canceled) is rejected under 35 USC 103(a) as being unpatentable over Nakabayashi et al. (US 2002/0033381) in view of EP 1178133. The Applicant respectfully disagrees, especially based on the amendments presented herein.

Claim 1 recites:

“A used PVD component refurbishing method comprising:

providing a used PVD component having a layer deposited on a component surface, wherein the component comprises a tantalum coil and the deposited layer comprises TaN deposited on the coil surface during PVD use;

first etching the deposited layer using a first acid-comprising etchant;

after the first etching, entraining abrasive particles in a flow of gas, impinging the particles on the etched layer, and abrading the etched layer; and

after the abrading, second etching the abraded layer using a second acid-comprising etchant.”

Nakabayashi does not disclose, teach or suggest that the component comprises a tantalum coil and that the deposited layer comprises TaN deposited on the coil surface, and the combination of Nakabayashi with EP 1178133 does not cure the deficiency in Nakabayashi. Therefore, claim 1 is patentable over the combination of Nakabayashi and EP 1178133, and claim 4 is also patentable over the combination of Nakabayashi and EP 1178133 based on its dependency on claim 1.

Claims 10 and 14 are rejected under 35 USC 103(a) as being unpatentable over Nakabayashi

et al. (US 2002/0033381) in view of Banholzer (US 5565058). The Applicant respectfully disagrees, especially based on the amendments presented herein.

Claim 1 recites:

“A used PVD component refurbishing method comprising:

providing a used PVD component having a layer deposited on a component surface, wherein the component comprises a tantalum coil and the deposited layer comprises TaN deposited on the coil surface during PVD use;

first etching the deposited layer using a first acid-comprising etchant;

after the first etching, entraining abrasive particles in a flow of gas, impinging the particles on the etched layer, and abrading the etched layer; and

after the abrading, second etching the abraded layer using a second acid-comprising etchant.”

Nakabayashi does not disclose, teach or suggest that the component comprises a tantalum coil and that the deposited layer comprises TaN deposited on the coil surface, and the combination of Nakabayashi with Banholzer does not cure the deficiency in Nakabayashi. Therefore, claim 1 is patentable over the combination of Nakabayashi and Banholzer, and claims 10 and 14 are also patentable over the combination of Nakabayashi and Banholzer based on their dependency on claim 1.

REQUEST FOR ALLOWANCE

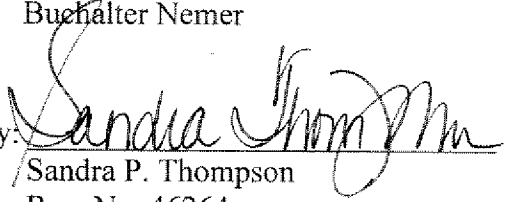
Claims 1-3, 5, 7 and 9-27 are pending in this application, and the Applicant respectfully requests that the Examiner reconsider all of the claims in light of the arguments presented and allow all current and pending claims.

Respectfully submitted,

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